IN THE CLAIMS

Please amend the claims as follows:

1. (currently amended) A method for producing a preform from synthetic quartz glass by means of a plasma-assisted deposition **process, said** method **comprising: supplying** [~~in that~~] a hydrogen-free media flow containing a glass starting material and a carrier gas [~~is supplied~~] to a multi-nozzle deposition burner, **introducing** the glass starting material [~~is introduced~~] by means of the deposition burner into a plasma zone [~~and is~~] **wherein the glass starting material is** oxidized **so as to form** [~~therein while forming~~] SiO_2 particles, and **depositing** the SiO_2 particles [~~are deposited~~] on a deposition surface while being directly vitrified, **wherein** [~~characterized in that~~] the media flow is focused by means of the deposition burner [~~(1)~~] towards the plasma zone [~~(4)~~].

2. (currently amended) The method according to claim 1, **wherein** [~~characterized in that~~] the media flow is focused onto the plasma zone [~~(4)~~] by means of a media nozzle [~~(7)~~] of the deposition burner [~~(1)~~] that **tapers in the direction of** [~~is tapering towards~~] the plasma zone [~~(4)~~].

3. (currently amended) The method according to claim 2, **wherein** [~~characterized in that~~] when exiting from the media nozzle [~~(7)~~] the media flow is enveloped by an oxygen-containing working gas flow.

4. (currently amended) The method according to claim 3, **wherein** [~~characterized in that~~] the working gas flow turbulently exits from a first working gas nozzle [~~(14)~~] of the deposition burner [~~(1)~~] that is designed as a diffuser.

5. (currently amended) The method according to claim 3, **wherein** [~~**characterized in that**~~] when exiting from the working gas nozzle [~~(14)~~] the working gas flow is enveloped by at least one oxygen-containing separating gas flow exiting from an annular gap nozzle [~~(17)~~] coaxially surrounding the working gas nozzle [~~(14)~~].

6. (currently amended) The method according to claim 3, **wherein** [~~**characterized in that**~~] the plasma zone [~~(4)~~] is produced by means of high-frequency excitation [~~(3)~~] inside a burner tube [~~(2)~~] into which a mixture of media flow and working gas flow is introduced.

7. (currently amended) The method according to claim 1, **wherein** [~~**characterized in that**~~] the **glass starting material in the** media flow contains silicon tetrachloride ($SiCl_4$) and **the carrier gas is** nitrogen [~~**as the carrier gas**~~].

8. (currently amended) The method according to claim 1, **wherein** [~~**characterized in that**~~] the glass starting material contains a fluorine-containing component.

9. (currently amended) A device for **producing a preform from synthetic quartz glass by means of a plasma-assisted deposition process** [~~**performing the method according to claim 1**~~], **said device** comprising an excitation source [~~**for**~~] producing a plasma zone, and a multi-nozzle deposition burner which has a central axis and which is provided with a media nozzle [~~**for the supply of**~~] **supplying** a **a hydrogen-free** media flow **containing a glass starting material and a carrier gas** to the plasma zone, **wherein** [~~**characterized in that**~~] the media nozzle [~~(7)~~] is configured to focus towards the plasma zone [~~(4)~~].

10. (currently amended) The device according to claim 9, **wherein** [~~**characterized in that**~~] the media nozzle [~~(7)~~] tapers in a tapering **portion** [~~**area (6)**~~] towards the plasma zone [~~(4)~~].

11. (currently amended) The device according to claim 10, **wherein** [~~**characterized in that**~~] the tapering **portion** [~~**area (6)**~~] has a length of at least 5 mm [~~**, preferably at least 8 mm**~~].

12. (currently amended) The device according to claim 9, **wherein** [~~**characterized in that**~~] the media nozzle [~~**(7)**~~] has a nozzle opening with a diameter ranging between 4.5 mm and 6.5 mm [~~**, preferably between 5.0 mm and 6.0 mm**~~].

13. (currently amended) The device according to claim 9, **wherein** [~~**characterized in that**~~] the media nozzle [~~**(7)**~~] is **configured** [~~**designed**~~] as a central middle nozzle and is coaxially surrounded by a working gas nozzle [~~**(14) in the form of**~~] **defining therebetween** an annular gap **and** which is **configured** [~~**designed**~~] as a diffuser and continuously expands in an expansion **portion** [~~**area**~~] towards the plasma zone [~~**(4)**~~].

14. (currently amended) The device according to claim 13, **wherein** [~~**characterized in that**~~] the expansion **portion** [~~**area**~~] has a length of at least 5 mm [~~**, preferably at least 8 mm**~~].

15. (currently amended) The device according to claim 12, **wherein** [~~**characterized in that**~~] the media nozzle [~~**(7)**~~] has a nozzle opening which extends in a first nozzle plane extending in a direction perpendicular to the central axis [~~**(9)**~~], and that the working gas nozzle [~~**(14)**~~] has a nozzle opening which extends in a second nozzle plane extending in a direction perpendicular to the central axis, the first nozzle plane, when viewed in the direction of flow, being arranged upstream of the second nozzle plane by a length between 5 mm and 35 mm [~~**, preferably between 13 mm and 33 mm**~~].

16. (currently amended) The device according to claim 9, **wherein** [~~**characterized in that**~~] the media nozzle [~~**(7)**~~] is formed by a quartz glass tube.

17. (currently amended) The device according to claim 9, **wherein** [~~characterized in that~~] the media nozzle [~~(7)~~] is designed as a central middle nozzle and is coaxially surrounded by at least two annular gap nozzles [~~(14; 17) for the supply of~~] **supplying** oxygen to the plasma zone [~~(4)~~]

18. (new) The device according to claim 10, wherein the tapering area has a length of at least 8 mm.

19. (new) The device according to claim 9, wherein the media nozzle has a nozzle opening with a diameter ranging between 5.0 mm and 6.0 mm.

20. (new) The device according to claim 13, wherein the expansion portion has a length of at least 8 mm.

21. (new) The device according to claim 12, wherein the media nozzle has a nozzle opening which extends in a first nozzle plane extending in a direction perpendicular to the central axis, and that the working gas nozzle has a nozzle opening which extends in a second nozzle plane extending in a direction perpendicular to the central axis, the first nozzle plane, when viewed in the direction of flow, being arranged upstream of the second nozzle plane by a length between 13 mm and 33 mm.